

Negative Staining Protocol:

Use Nano-W stain (2 % Methylamine Tungstate) or 2% uranyl acetate (UA)

1. Loaded 4 μL sample solution onto carbon film for 1 min, and removed the excess solution was by filter paper
2. Washing one time with ddH₂O
3. Sample was stained with 4 μL 2 % Nano-W or 2 % uranyl acetate (UA) for 1 min (incubate time depends on sample concentration). Because UA is a light-sensitive stain, prevent the UA solution from light (especially UV light)
4. The residual stain solution was removed by filter paper
5. Stored in humidity control box and dry overnight

負染色流程：

可使用 Nano-W 染劑 (2 % Methylamine Tungstate)或 2%醋酸鈾 (Uranyl Acetate, UA)

1. 在銅網上滴 4 μL 樣品反應 1 分鐘後，用濾紙吸掉多餘樣品 (銅網可先經過親水性處理)
2. 用 ddH₂O 清洗一次 (清洗次數可以調整)
3. 滴上 4 μL 的 2 %Nano-W 或 2 % 醋酸鈾染劑反應 1 分鐘 (培養時間可視樣品濃度作調整)，使用 UA 染色過程需注意避光
4. 用濾紙吸掉多餘的染劑
5. 染色完後可照光 6 分鐘加速乾燥，最後存放至防潮箱乾燥一晚，隔天可 TEM 上機